

DECLARATION OF JOINT INVENTORS FOR PATENT APPLICATION

As the below named inventor, I hereby declare that:

My residence, post office address and citizenship are as stated below next to my name.

I believe I am the original, first and joint inventor of the subject matter which is claimed and for which a patent is sought on the invention entitled: **Plasma Etching Process And Chemical Vapor Deposition Process Of Depositing A Material Over A Semiconductor Substrate**, the specification of which is attached hereto.

I hereby state that I have reviewed and understand the contents of the above-identified specification, including the claims.

I acknowledge the duty to disclose information known to me to be material to patentability as defined in Title 37, Code of Federal Regulations §1.56.

**PRIOR FOREIGN APPLICATIONS:**

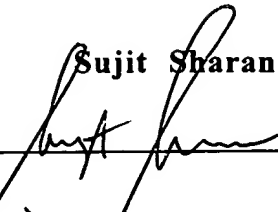
I hereby state that no applications for foreign patents or inventor's certificates have been filed prior to the date of execution of this declaration.

I hereby declare that all statements made herein of my own knowledge are true and that all statements made on information and belief are believed to be true; and further that these statements were made with the knowledge that willful false statements and the like so made are punishable by fine or imprisonment, or both, under Section 1001 of Title 18 of the United States Code and that such willful

false statement may jeopardize the validity of the application or any patent issued therefrom.

\* \* \* \* \*

Full name of inventor: **Sujit Sharan**

Inventor's Signature: 

Date: July 8, 1999

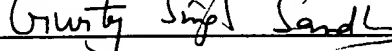
Residence: **Boise, Idaho**

Citizenship: **India**

Post Office Address: **5683 S. Alyssum Place  
Boise, ID 83706**

\* \* \* \* \*

Full name of inventor: **Gurtej S. Sandhu**

Inventor's Signature: 

Date: July 6, 1999

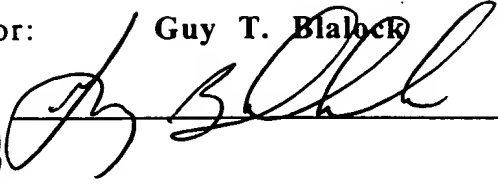
Residence: **Boise, Idaho**

Citizenship: **U.K.**

Post Office Address: **2964 E. Parkriver Drive  
Boise, ID 83706**

\* \* \* \* \*

Full name of inventor: Guy T. Blalock

Inventor's Signature: 

Date: 7/16/99

Residence: Boise, Idaho

Citizenship: U.S.A.

Post Office Address: 8101 Silkwood Court  
Boise, ID 83704

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. . . . . Filed Herewith  
Filing Date . . . . . Filed Herewith  
Inventor . . . . . Sujit Sharan et al.  
Assignee . . . . . Micron Technology, Inc.  
Group Art Unit . . . . . Unassigned  
Examiner . . . . . Unassigned  
Attorney's Docket No. . . . . MI22-1106  
Title: Plasma Etching Process And Chemical Vapor Deposition Process Of  
Depositing A Material Over A Semiconductor Substrate

**POWER OF ATTORNEY BY ASSIGNEE AND**  
**CERTIFICATE BY ASSIGNEE UNDER 37 CFR §3.73(b)**

To: Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

MICRON TECHNOLOGY, INC., the Assignee of the entire right,  
title and interest in the above-identified patent application by assignment  
attached hereto, hereby appoints the attorneys and agents of the firm  
of WELLS, ST. JOHN, ROBERTS, GREGORY & MATKIN P.S., listed  
as follows:

Richard J. St. John	Reg. No. 19,363
David P. Roberts	Reg. No. 23,032
Randy A. Gregory	Reg. No. 30,386
Mark S. Matkin	Reg. No. 32,268
James L. Price	Reg. No. 27,376
Deepak Malhotra	Reg. No. 33,560
Mark W. Hendricksen	Reg. No. 32,356
David G. Latwesen	Reg. No. 38,533
George G. Grigel	Reg. No. 31,166
Keith D. Grzelak	Reg. No. 37,144
Lance R. Sadler	Reg. No. 38,605
James D. Shaurette	Reg. No. 39,833

and also attorneys Michael L. Lynch (Reg. No. 30,871) and Lia Pappas  
Dennison (Reg. No. 34,095) of Micron Technology, Inc., as its attorneys

1 with full power of substitution to prosecute this application and transact  
2 all business in the Patent and Trademark Office connected therewith.

3 The Assignee certifies that the above-identified Assignment has  
4 been reviewed and to the best of Assignee's knowledge and belief, title  
5 is in the Assignee.

6 Please direct all correspondence regarding this application to:

7 Wells, St. John, Roberts, Gregory & Matkin P.S.  
8 Attn: Mark S. Matkin  
9 601 W. First Avenue, Suite 1300  
10 Spokane, WA 99201-3828

11 Telephone: (509) 624-4276  
12 Facsimile: (509) 838-3424

13 MICRON TECHNOLOGY, INC.

14 Dated: July 2, 1995

15 By: [Signature]

16 Name: Michael L. Lynch, Esq.  
17 Title: Chief Patent Counsel  
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